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(54) Title (EN): POLYMER ALLOY, CROSSLINKED OBJECT, AND INDUSTRIAL PART

(54) Title (FR): ALLIAGE POLYMERES, OBJET RETICULE, ET PIECE INDUSTRIELLE ASSOCIEE

(54) Title (JA): ポリマーアロイ、架橋物および工業部品

(57) Abstract:

(EN): A polymer alloy which comprises (A) 5 to 88 wt.% ##-ethylenically unsaturated nitrile/conjugated diene copolymer rubber having a number-average molecular weight of 50,000 to 150,000, (B) 10 to 60 wt.% acrylic copolymer having units derived from an ##-ethylenically unsaturated nitrile monomer, and (C) 2 to 50 wt.% ##-ethylenically unsaturated nitrile/conjugated diene copolymer rubber having a number-average molecular weight of 1,000 to 20,000. The polymer alloy is excellent in oil resistance and ozone resistance and also in resistance to cracking caused by solvents.

(FR): L'invention concerne un alliage polymère comprenant: (A) 5 à 88 % en poids de caoutchouc de copolymère de diène conjugué/nitrile ## éthyléniquement insaturé, présentant un poids moléculaire moyen en nombre compris entre 50 000 et 150 000 ; (B) 10 à 60 % en poids d'un copolymère acrylique présentant des unités dérivées d'un monomère de nitrile ## éthyléniquement insaturé ; et (C) 2 à 50 % en poids de caoutchouc de copolymère de diène conjugué/nitrile ## éthyléniquement insaturé présentant un poids moléculaire moyen en nombre compris entre 1 000 et 20 000. Cet alliage polymère présente une excellente résistance à l'huile et une excellente résistance à l'ozone, ainsi qu'une excellente résistance au craquage provoqué par des solvants.

(JA): 数平均分子量 50,000 ~ 150,000 の α,β -エチレン性不飽和二トリル-共役ジエン共重合ゴム(A) 5 ~ 8 重量%、 α,β -エチレン性不飽和二トリル単量体単位を含有するアクリル共重合体(B) 10 ~ 60 重量%、および数平

均分子量 1,000 ~ 20,000 の α,β -エチレン性不飽和ニトリル-共役ジエン共重合ゴム(C)2 ~ 50 重量%から成るポリマーアロイ。この発明によると、耐油性及び耐オゾン性に優れ、かつ、耐溶剤亀裂性にも優れるポリマーアロイを提供することができる。

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